

Attorney Docket No. Patent 81329A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of: JOSEPH J. DANKO

Serial No: 09/579,593

Group Art Unit: 2877

Filed: May 26, 2000

Examiner: G. J. Stock, Jr.

For: METHOD AND APPARATUS FOR INSPECTING A PATTERNED
SEMICONDUCTOR WAFER

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Commissioner for Patents
P.O. Box 1450
Alexandria, Va 22313-1450

JUL 16 2003

TECHNOLOGY CENTER 2800

Dear Sir:

SUPPLEMENTAL AMENDMENT

This communication is further to an Amendment on this application mailed to the U.S. Patent and Trademark Office on June 3, 2003. It is respectfully requested that the above-identified application be amended as follows:

IN THE CLAIMS:

Please change the marked up version of claim 19 appearing on pages 20 and 21 in the Amendment dated June 3, 2003 to read as follows:

19. (Twice Amended) A method for detecting the presence of contaminant particles on a semiconductor wafer having repetitive patterns, said method comprising:

[a.] (a) illuminating a pair of intersecting stripe shaped regions on the semiconductor wafer, using a pair of beams of light, each beam of light having an approach angle and an angle of incidence that is angularly adjustable independent of the approach angle and angle of incidence of the other beam of light, and